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By: *Linda K. Heston*

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Attorney Docket No.: NEKW14.868

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

May 1, 2000

Assistant Commissioner for Patents
Washington, D.C. 20231

AMENDMENT

SIR:

In response to the Office Action dated February 2, 2000, the period for responding thereto having been set to expire on May 2, 2000, please amend the subject application as follows:

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